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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/665,515	09/16/2003	Takashi Matsuoka	96790P439	5830
8791	8791 7590 08/16/2005		EXAMINER	
BLAKELY SOKOLOFF TAYLOR & ZAFMAN 12400 WILSHIRE BOULEVARD SEVENTH FLOOR			GOLUB, MARCIA A	
			ART UNIT	PAPER NUMBER
LOS ANGEI	LOS ANGELES, CA 90025-1030		2828	:
			DATE MAILED: 08/16/2005	

Please find below and/or attached an Office communication concerning this application or proceeding.

	Application No.	Applicant(s)			
	10/665,515	MATSUOKA ET AL.			
Office Action Summary	Examiner	Art Unit			
	Marcia A. Golub	2828			
The MAILING DATE of this communication app Period for Reply	ears on the cover sheet with the c	orrespondence address			
A SHORTENED STATUTORY PERIOD FOR REPLY	/ IS SET TO EXPIRE 3 MONTH(S) FROM			
 THE MAILING DATE OF THIS COMMUNICATION. Extensions of time may be available under the provisions of 37 CFR 1.13 after SIX (6) MONTHS from the mailing date of this communication. If the period for reply specified above is less than thirty (30) days, a reply If NO period for reply is specified above, the maximum statutory period with the set or extended period for reply will, by statute, Any reply received by the Office later than three months after the mailing earned patent term adjustment. See 37 CFR 1.704(b). 	within the statutory minimum of thirty (30) day will apply and will expire SIX (6) MONTHS from cause the application to become ABANDONE	s will be considered timely. the mailing date of this communication. D (35 U.S.C. § 133).			
Status	•				
1)⊠ Responsive to communication(s) filed on 16 Se	eptember 2003.				
·	Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under <i>Ex parte Quayle</i> , 1935 C.D. 11, 453 O.G. 213.				
Disposition of Claims					
4)⊠ Claim(s) <u>1-19</u> is/are pending in the application.					
4a) Of the above claim(s) is/are withdrawn from consideration.					
5) Claim(s) is/are allowed.	•				
6)⊠ Claim(s) <u>1-19</u> is/are rejected.					
7) Claim(s) is/are objected to.	•				
8) Claim(s) are subject to restriction and/or	r election requirement.				
Application Papers					
9)☐ The specification is objected to by the Examine	r.				
10)⊠ The drawing(s) filed on 16 September 2003 is/a	are: a)⊠ accepted or b)⊡ objec	ted to by the Examiner.			
Applicant may not request that any objection to the					
Replacement drawing sheet(s) including the correct 11) The oath or declaration is objected to by the Ex	•				
Priority under 35 U.S.C. § 119					
12)⊠ Acknowledgment is made of a claim for foreign a)⊠ All b)□ Some * c)□ None of:	priority under 35 U.S.C. § 119(a))-(d) or (f).			
 a) All b) Some * c) None of: 1. Certified copies of the priority documents 	s have been received				
2. Certified copies of the priority document		on No			
3. Copies of the certified copies of the prior					
application from the International Bureau	•	72 2.10			
* See the attached detailed Office action for a list	, , , ,	ed.			
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Attachment(s)	A) 🗀 Jahan dawa Owan	(DTO 412)			
Notice of References Cited (PTO-892) Notice of Draftsperson's Patent Drawing Review (PTO-948)	4) Interview Summary Paper No(s)/Mail Da				
3) ☑ Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08) Paper No(s)/Mail Date 10/16/03,3/18/05. 5/3 / 05		atent Application (PTO-152)			

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DETAILED ACTION

Claim Rejections - 35 USC § 102

The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

(e) the invention was described in (1) an application for patent, published under section 122(b), by another filed in the United States before the invention by the applicant for patent or (2) a patent granted on an application for patent by another filed in the United States before the invention by the applicant for patent, except that an international application filed under the treaty defined in section 351 (a) shall have the effects for purposes of this subsection of an application filed in the United States only if the international application designated the United States and was published under Article 21(2) of such treaty in the English language.

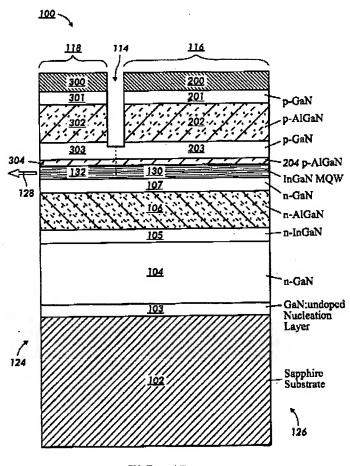


FIG. 4B

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Claims 1-19 are rejected under 35 U.S.C. 102(e) as being anticipated by Kneissl et al. (U.S.Pat. 6,526,083).

Regarding **claims 1-3, 11, and 12,** Fig. 4B of Kneissl discloses "a laser [116] with an optical modulator [118], which are integrated on a single substrate [102] wherein optical modulator comprises:

a lower cladding layer of a first conductivity type [106, n-type]; a light absorption layer [108] which is formed on said lower cladding layer and has a quantum-well structure constituted by a quantum-well layer and a barrier layer [column 5 lines 12-18 and column 7 lines 22-25]; and an upper cladding layer [110, p-type] of a second conductivity type formed on said light absorption layer,

wherein the quantum-well layer is made of $ln_{1-x-y}Ga_xAl_yN$ ($0\le x,y\le 1$, $0\le x+y\le 1$) [InGaN when x=1, y=0, column 5 lines 12-13], the barrier layers is made of $ln_{1-x'-y'}Ga_xAl_yN$ ($0\le x',y'\le 1$, $0\le x'+y'\le 1$) [GaN when y'=0 x'=1, column 5 line 17],

and an optical waveguide having a light incident end is constituted by said lower cladding layer, said light absorption layer, and said upper cladding layer. [optical waveguide structure is inherent to optical modulators]

wherein said light absorption layer includes a multiple-quantum-well structure [column 5 lines 12-18],

wherein said lower cladding layer is formed on a predetermined substrate" [102]

Regarding claims 4-6 and 13-15, Kneissl discloses a nitride semiconductor

device as described above with inherent polarization properties "wherein polarization is produced in said light absorption layer in the absence of a bias, wherein the polarization

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is spontaneous polarization produced in said light absorption layer, wherein the polarization is the sum of spontaneous polarization and piezoelectric polarization produced in said light absorption layer."

Spontaneous and piezoelectric polarizations are effects that occur due to the structure and composition of the materials and not due to applied voltage. Spontaneous polarization occurs due to wurtzite structure of nitride-based III-V semiconductors. Since both InN and InGaN materials have wurtzite structure, spontaneous polarization occurs in the active layer. Piezoelectric polarization occurs due to the compressive strain in the material that results from the lattice mismatch between different layers. Since the lattice constant of InGaN is larger than the lattice constant of GaN, quantum well layer is compressively stained producing piezoelectric polarization in the same direction as spontaneous polarization. Therefore the total polarization is the sum of spontaneous and piezoelectric polarization.

Regarding **claims 7, 8, 16, and 17**, Kneissl discloses everything claimed, as applied above, in addition "the quantum-well layer and the barrier layer have different lattice constants, wherein the quantum-well layer has a larger lattice constant than the barrier layer [InGaN has a larger lattice constant than GaN, column 5 lines 12-18].

Regarding **claims 9, 10, 18, and 19** Kneissl discloses a nitride semiconductor device as described above wherein the quantum well layer comprises InGaN and barrier layer comprises GaN. Even though the reference does not disclose the specific composition of InGaN, it is well known in the art that the composition of ternary

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compounds varies according to the formula $A_xB_{1-x}C$ $0 \le x \le 1$. Therefore, the reference inherently discloses the quantum well layer comprising $In_xGa_{1-x}N$, and in the case of x=1 the quantum well layer can be InN. Also, since the concentration of In and Ga can vary from 0 to 1 quantum well layer material can have different lattice constants. Therefore, the quantum-well layer can have a smaller lattice constant than the barrier layer.

Fax/Telephone Information

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Marcia A. Golub whose telephone number is 571-272-0218. The examiner can normally be reached on M-F 8-5 pm.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Minsun Harvey can be reached on 571-272-1835. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306. Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

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